



PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR
REMOVING PHOTORESIST AND/OR
RESIST RESIDUE AT PRESSURES
RANGING FROM AMBIENT TO
SUPERCritical

Confirmation No.: 8934

Group Art Unit: 1746

Examiner: B.S. Carrillo

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(37 CFR 1.8(a))**

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450 on Sept. 27, 2004.
STALLMAN & POLLOCK LLP

Dated: 09/27/2004 By: Georgia K. Smith
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Atty Docket No.: SCP-9410